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### (54) PHOTSENSITIVE AND HEAT SENSITIVE RECORDING MATERIAL

#### (57)Abstract:

**PROBLEM TO BE SOLVED:** To ensure superior sensitivity, shelf stability and development latitude by successively disposing a 1st layer containing a water-insoluble and alkaline water-soluble polymer and a 2nd layer having a polarity changing material which changes from a lipophilic material into a hydrophilic material under heat on a substrate.

**SOLUTION:** A 1st layer containing a water-insoluble and alkaline water-soluble polymer and a 2nd layer having a polarity changing material which changes from a lipophilic material into a hydrophilic material under heat are successively disposed on a substrate. Since the polarity changing material is used in the surface layer which generates large heat, the penetrating property of a developing solution is enhanced, the difference in dissolution rate between exposed and unexposed parts is increased and high sensitivity is ensured. The developing solution penetrates from the surface layer to the interface of the substrate even after preservation because of its high penetrating property and develops even the water-insoluble and alkaline water-soluble polymer highly associated near the interface and shelf stability is improved.

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